

Title (en)

Method for making a high performance bipolar transistor in an integrated circuit.

Title (de)

Verfahren zum Herstellen eines hochwertigen bipolaren Transistors in einer integrierten Schaltung.

Title (fr)

Procédé de fabrication d'un transistor bipolaire de grande performance dans un circuit intégré.

Publication

**EP 0089503 A2 19830928 (EN)**

Application

**EP 83101755 A 19830223**

Priority

US 36073182 A 19820322

Abstract (en)

A process is described which permits the fabrication of very narrow base width bipolar transistors. The ability to selectively vary the transistor characteristics provides a degree of freedom for design of integrated circuits. The bipolar transistor is processed up to the point of emitter formation using conventional techniques. But, prior to the emitter formation, a portion of the base area (22) wherein the emitter region (34) is planned to be formed is dry etched using reactive ion etching. The existing silicon nitride/silicon dioxide layers (24, 26) with the emitter opening (30) therein are used as the etching mask for this reactive ion etching procedure. Once the etching is completed to the desired depth, the normal processing is resumed to form the emitter and rest of the metallization. Since the intrinsic base under the emitter (34) is etched, and the normal emitter is formed afterwards, the etching reduces the base width by an amount approximately equal to the etched depth. The transistor characteristics depend strongly upon the base width so the etching is controlled to very tight dimensions.

IPC 1-7

**H01L 29/10**; **H01L 29/72**

IPC 8 full level

**H01L 29/73** (2006.01); **H01L 21/3065** (2006.01); **H01L 21/331** (2006.01); **H01L 29/10** (2006.01); **H01L 29/732** (2006.01)

CPC (source: EP US)

**H01L 21/3065** (2013.01 - EP US); **H01L 29/1004** (2013.01 - EP US); **H01L 29/7325** (2013.01 - EP US)

Cited by

EP0089504A3; CN112053952A; GB2243717A; GB2243717B

Designated contracting state (EPC)

DE FR GB

DOCDB simple family (publication)

**EP 0089503 A2 19830928**; **EP 0089503 A3 19860917**; **EP 0089503 B1 19890913**; DE 3380583 D1 19891019; JP S58168276 A 19831004; US 4435898 A 19840313

DOCDB simple family (application)

**EP 83101755 A 19830223**; DE 3380583 T 19830223; JP 20220582 A 19821119; US 36073182 A 19820322